

Form PTO 1449 U.S. DEPARTMENT OF COMMERCE
(Modified) PATENT AND TRADEMARK OFFICE

ATTY. DOCKET NO.

8733.215.00

08/671,376

APPLICANT

Tieer GU et al.

FILING DATE

June 27, 1996

GROUP

2822

LIST OF REFERENCES CITED BY APPLICANT
(Use Several Sheets if Necessary)

Date: February 5, 2001

U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
<i>QMD</i>	AA	6,100,954	08/08/00	Kim et al.	349	138	
<i>QMD</i>	AB	4,636,038	01/1987	Kitahara et al.	350	339	
<i>QMD</i>	AC	4,943,838	07/1990	Ukai	257	410	
<i>QMD</i>	AD	5,072,262	12/1991	Uekita et al.	257	410	
<i>QMD</i>	AE	5,229,644	07/1993	Wakai et al.	257	749	
<i>QMD</i>	AF	5,246,782	09/1993	Kennedy et al.	428	421	
<i>QMD</i>	AG	5,294,820	03/1994	Gemma et al.	257	324	
<i>QMD</i>	AH	5,486,493	01/1996	Jeng	437	195	

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION YES	TRANSLATION NO
<i>QMD</i>	AI	63-279228	11/1988	JAPAN		
<i>QMD</i>	AJ	63-289965	11/1988	JAPAN		
<i>QMD</i>	AK	04-068318	03/1992	JAPAN		
<i>QMD</i>	AL	04-163528	06/1992	JAPAN		
<i>QMD</i>	AM	05-203936	08/1993	JAPAN		

OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, Etc.)

<i>QMD</i>	AN	M.J. Radler et al., Cyclotene™ Advanced Electronics Resins for High-Aperture AMLCD Applications, SID 96 APPLICATIONS DIGEST, pp. 33-36 (1996).
<i>QMD</i>	AO	Eric P. Finchem et al., A Multi-Level High Density Interconnect Process Designed & Developed for Manufacturability, TriQuint Semiconductor, Inc., Beaverton, OR, USA
<i>QMD</i>	AP	M.J. Radler et al., Benzocyclobutene Dielectric Resins for Flat Panel Display Applications, Proceedings of the 3 rd Annual Display Manufacturing Technology Conference, pp: 123-4, 1996 (Conference date: February 6-8, 1996)

EXAMINER

DATE CONSIDERED

2/28/03

*EXAMINER: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

**English-language abstract provided.

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LIST OF REFERENCES CITED BY APPLICANT (Use Several Sheets if Necessary) Date: <u>January 29, 2001</u>		APPLICANT Tieer GU et al.					
		FILING DATE June 27, 1996	GROUP 2822				
U.S. PATENT DOCUMENTS							
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
<i>JMD</i>	BA	5,585,951	12/1996	Noda et al.	349	122	
<i>JMD</i>	BB	5,591,676	01/1997	Hughes et al.	438	702	
<i>JMD</i>	BC	5,641,974	06/1997	Den Boer et al.	257	59	
<i>JMD</i>	BD	5,675,187	10/1997	Numata et al.	257	758	
<i>JMD</i>	BE	5,721,596	02/1998	Kochi	349	2	
<i>JMD</i>	BF	5,721,601	02/1998	Yamaji et al.	349	138	
<i>JMD</i>	BG	5,821,621	10/1998	Jeng	257	759	
<i>JMD</i>	BH	6,038,008	03/14/2000	Kim et al.	349	138	08/964,914 - 11/05/1997
FOREIGN PATENT DOCUMENTS							
		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION YES NO		
<i>JMD</i>	BI	0-536-898 A1	04/1993	EUROPEAN PATENT OFFICE (In English)			
<i>JMD</i>	BJ	0-589-478 A2	03/1994	EUROPEAN PATENT OFFICE (In English)			
<i>JMD</i>	BK	0-589-478 A3	03/1994	EUROPEAN PATENT OFFICE (In English)			
<i>JMD</i>	BL	0-486-047 A2	05/1992	EUROPEAN PATENT OFFICE (In English)			
<i>JMD</i>	BM	0-486-047 A3	05/1992	EUROPEAN PATENT OFFICE (In English)			
OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, Etc.)							
<i>JMD</i>	BN	Stanley Wolf et al., <i>Silicon Processing For The VLSI Era</i> , Vol. 1, Process Technology, Lattice Press, Sunset Beach, CA., 1986					
<i>JMD</i>	BO	Tadanori Shimoto et al. <i>High Density Multilayer Substrate Using Benzocyclobutene Dielectric</i> , IMC 1992 Proceedings, Yokohama, June 3-5, 1992, pp: 325-30					
<i>JMD</i>	BP	Willem den BOER et al., <i>High Aperture TFT LCD using Polymer Interlevel Dielectric</i> , OIS Optical Imaging Systems, Inc., Northville, MI, USA					
EXAMINER: <i>Stanley M. Wolf</i>					DATE CONSIDERED <i>2/28/03</i>		
<p>*EXAMINER: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</p> <p>**English-language abstract provided.</p>							

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U.S. PATENT DOCUMENTS

EXAMINER INITIAL	CA	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
<i>QMD</i>	CA	4,431,272	02/1984	Yazawa et al.	350	336	
<i>QMD</i>	CB	4,451,525	05/1984	Kawazoe et al.	428	213	
<i>QMD</i>	CC	5,408,345	04/1995	Mitsui et al.	349	42	
<i>QMD</i>	CD	5,411,629	05/1995	Warfield	216	34	
<i>QMD</i>	CE	5,500,750	03/1996	Kanbe et al.	349	42	
<i>QMD</i>	CF	5,600,458	02/1997	Okano et al.	349	44	
<i>QMD</i>	CG	5,724,111	03/1998	Mizobata et al.	349	113	
<i>QMD</i>	CH	5,844,647	12/1998	Maruno et al.	349	138	

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION YES	NO
<i>QMD</i>	CI	0-616-241 A2	09/1994	EUROPEAN PATENT OFFICE (In English)		
<i>QMD</i>	CJ	0-714-140 A1	05/1996	EUROPEAN PATENT OFFICE (In English)		
<i>QMD</i>	CK	2-311-653	10/1997	UNITED KINGDOM (In English)		
<i>QMD</i>	CL	41-40-180 A1	12/1992	DENMARK		
<i>QMD</i>	CM	4-257826A	09/1992	JAPAN (English Abstract only)		

OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, Etc.)

<i>QMD</i>	CN	M.W. Friends, <i>Determination of Dielectric Constant for Fuji Clear</i> , 3/7/1996, pp:1-2, including Table
<i>QMD</i>	CO	Willem den BOER, <i>A Two-Diode Pixel Circuit and Addressing Method for MIM LCDs</i> , OIS Optical Systems, Inc., Northville, MI, USA
<i>QMD</i>	CP	Tech Notes, Advanced Electronics Resins, <i>Processing Guide for Photo-Imageable BCB</i> , Dow Chemical Co., pp: 1-4

EXAMINER <i>James M. Ho</i>	DATE CONSIDERED <u>2/28/03</u>
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U.S. PATENT DOCUMENTS							
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
<i>JMD</i>	DA	5,177,588	01/05/1993	li et al.	257	640	
<i>JMD</i>	DB	5,045,905	09/03/1991	Motai et al.	357	207	
<i>JMD</i>	DC	5,281,546	01/25/1994	Possin et al.	437	40	
<i>JMD</i>	DD	5,003,356	03/26/1991	Wakai et al.	357	4	
<i>JMD</i>	DE	5,847,720	12/08/1998	Dunand	347	1	
<i>JMD</i>	DF	5,576,630	11/19/1996	Fujita	324	760	
<i>JMD</i>	DD	5,920,084	07/06/1999	Gu et al.	257	59	
<i>JMD</i>	DH	5,780,874	07/14/1998	Kudo	257	77	

FOREIGN PATENT DOCUMENTS					
		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION YES NO
<i>JMD</i>	DI	10-133165	05/1998	JAPAN	
	DJ				
	DK				
	DL				
	DM				

OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, Etc.)		
<i>JMD</i>	DN	Michael Schier, <i>Reactive Ion Etching of Benzocyclobutene Using a Silicon Nitride Dielectric Etch Mask</i> , J. Electrochem. Soc., Vol. 142, No. 9, September 1995, pp: 3238-40
<i>JMD</i>	DO	Donald Peretrie, et al., <i>Benzocyclobutene as a Planarization Resin for Flat Panel Displays</i> , SPIE Vo., 1965, Liquid Crystal Materials, Device, and Applications (1992), pp: 331-7
	DP	

EXAMINER <i>Jennifer M. Dola</i>	DATE CONSIDERED <u>2/28/03</u>
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U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
<i>QMD</i>	EA	5,477,359	12/19/1995	Okazaki	359	77	
<i>QMD</i>	EB	5,287,208	02/15/1994	Shimoto et al.	359	75	
<i>QMD</i>	EC	5,994,721	11/30/1999	Zhong et al.	257	89	
	ED						
	EE						
	EF						
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	EH						

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	TRANSLATION	
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	EI					
	EJ					
	EK					
	EL					
	EM					

OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER	<i>Quinlan M. Dolan</i>	DATE CONSIDERED	<i>4/28/03</i>
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Notice of References Cited

Application No.
08/671,376

Gu et al

Examiner
Michael Trinh

Group Art Unit
2822

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U.S. PATENT DOCUMENTS

	DOCUMENT NO.	DATE	NAME	CLASS	SUBCLASS
A	5,477,359	12/19/95	Okazaki	359	77
B	5,559,055	9/24/96	Chang et al	438	586
C	5,780,874	7/14/98	Kudo	257	642
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FOREIGN PATENT DOCUMENTS

	DOCUMENT NO.	DATE	COUNTRY	NAME	CLASS	SUBCLASS
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NON-PATENT DOCUMENTS

	DOCUMENT (Including Author, Title, Source, and Pertinent Pages)	DATE
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Notice of References Cited

Application No.
08/671,376

Gu et al

Examiner
Michael Trinh

Group Art Unit
2813

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U.S. PATENT DOCUMENTS

	D CUMENT NO.	DATE	NAME	CLASS	SUBCLASS
<i>Handwritten</i>	5,466,535	11/14/95	Higgins et al	428	483
<i>Handwritten</i>	5,477,380	12/19/95	Sunohara et al	349	132
<i>Handwritten</i>	5,585,951	12/17/96	Noda et al	349	122
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FOREIGN PATENT DOCUMENTS

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NON-PATENT DOCUMENTS

	DOCUMENT (Including Author, Title, Source, and Pertinent Pages)	DATE
<i>Handwritten</i>	Wolf et al, "Silicon Processing for the VLSI Era", vol 1, pp 407-408,418-421,428-429	1986
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Sheet 1 of 1

Patent and Trademark Office; U.S. DEPARTMENT OF COMMERCE

Sheet 1 of 1

Patent and Trademark Office; U.S. DEPARTMENT OF COMMERCE

Section 2. Form PTO - 1449 (Modified)

FORM PTO-1449 U.S. DEPARTMENT OF COMMERCE
(Modified) PATENT AND TRADEMARK OFFICE

INFORMATION DISCLOSURE
STATEMENT BY APPLICANT

(Use several sheets if necessary)

(37 CFR 1.98(b))

ATTY. DOCKET NO.

12190.293

SERIAL NO.

08/671,376

APPLICANT

den BOER, ET. AL.

FILING DATE

6/27/96

GROUP

U.S. PATENT DOCUMENTS

EXAMINER INITIAL	PATENT NUMBER	ISSUE DATE	PATENTEE	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
<i>QMN</i>	5 0 0 3 3 5 6	3/91	WAKAI, ET. AL.			
<i>QMN</i>	5 3 0 2 9 8 7	4/94	KANEMORI, ET. AL.			
<i>QMN</i>	5 4 1 4 2 7 8	5/95	KOBAYASHI, ET. AL.			
<i>QMN</i>	5 4 6 3 2 3 0	10/95	NEGOTO, ET. AL.			
<i>QMN</i>	5 4 6 3 4 8 4	10/95	BRODY			
<i>QMN</i>	5 5 2 8 2 0 9	6/96	MACDONALD, ET. AL.			

FOREIGN PATENT OR PUBLISHED FOREIGN PATENT APPLICATION

DOCUMENT NUMBER	PUBLICATION DATE	COUNTRY OR PATENT OFFICE	CLASS	SUBCLASS	TRANSLATION YES NO

OTHER DOCUMENTS (Including Author, Title, Date**, Relevant Pages, Place of Publication***)

EXAMINER

Quayle M. Dot

DATE CONSIDERED

2/29/03

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JC879 U.S. PTO
10/052767
01/23/02

Section 2. Form PTO - 1449 (Modified)

FORM PTO-1449 U.S. DEPARTMENT OF COMMERCE (Modified) PATENT AND TRADEMARK OFFICE INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use several sheets if necessary) (37 CFR 1.98(b))	ATTY. DOCKET NO. 12190.293	SERIAL NO. 08/671,376
	APPLICANT den BOER, ET. AL.	
	FILING DATE 6/27/96	GROUP

U.S. PATENT DOCUMENTS

[illegible]

FOREIGN PATENT OR PUBLISHED FOREIGN PATENT APPLICATION

[illegible]

OTHER DOCUMENTS (Including Author, Title, Date, Relevant Pages, Place of Publication)

JMD		"OPTIMISATION OF VERY SMALL PITCH ACTIVE MATRIX LCD FOR PROJECTION" BY VIGNOLLE, ET. AL., IBEE, 1991
JMD		"A HIGH-APERTURE-RATIO 3-IN.-DIAGONAL YGA A-SI LIGHT VALVE WITH PIXEL/DATA AND PIXEL/GATE LINES OVERLAPPING" BY SAKAMOTO, ET. AL. SID 1996 DIGEST
JMD		"HIGH APERTURE AND FAULT-TOLERANT PIXEL STRUCTURE FOR TFT-LCDs" BY KIM, ET. AL., SID 1995 DIGEST

EXAMINER	DATE CONSIDERED
<i>Amber M. Dotson</i>	<i>2/28/03</i>

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